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APPLICATION NO	F	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/501,762		07/19/2004	Wataru Hattori	8040-1059	2934	
466	7590	05/27/2005		EXAMINER		
YOUNG (	& THOMI	PSON		MULPURI,	SAVITRI	
745 SOUT	H 23RD ST	TREET				
2ND FLOO	)R			ART UNIT	PAPER NUMBER	
ARLINGT	ON, VA	22202		2812		

DATE MAILED: 05/27/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

			Ak
	Application No.	Applicant(s)	
	10/501,762	HATTORI, WATARU	
Office Action Summary	Examiner	Art Unit	
	Savitri Mulpuri	2812	
The MAILING DATE of this communication Period for Reply	appears on the cover sheet w	rith the correspondence address	; ••
A SHORTENED STATUTORY PERIOD FOR RE THE MAILING DATE OF THIS COMMUNICATIO  - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication.  - If the period for reply specified above is less than thirty (30) days, a  - If NO period for reply is specified above, the maximum statutory per  - Failure to reply within the set or extended period for reply will, by state of the provided by the Office later than three months after the meanned patent term adjustment. See 37 CFR 1.704(b).	N. R 1.136(a). In no event, however, may a reply within the statutory minimum of third will apply and will expire SIX (6) MO atute, cause the application to become A	reply be timely filed  irty (30) days will be considered timely.  NTHS from the mailing date of this communi BANDONED (35 U.S.C. § 133).	ication.
Status			
1) Responsive to communication(s) filed on 19	9 July 2004.		
2a) This action is <b>FINAL</b> . 2b) ⊠ T	his action is non-final.		
3) Since this application is in condition for allo	wance except for formal mat	iters, prosecution as to the mer	its is
closed in accordance with the practice unde	er <i>Ex par</i> te Q <i>uayle</i> , 1935 C.I	O. 11, 453 O.G. 213.	
Disposition of Claims			
4) ☑ Claim(s) 1-8 is/are pending in the application 4a) Of the above claim(s) is/are without 5) ☐ Claim(s) is/are allowed. 6) ☑ Claim(s) 1-8 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and	drawn from consideration.		
Application Papers			
9)☐ The specification is objected to by the Exam	niner.		
10) The drawing(s) filed on is/are: a) a	accepted or b)⊡ objected to	by the Examiner.	
Applicant may not request that any objection to	*	• •	
Replacement drawing sheet(s) including the cor	· · · · · · · · · · · · · · · · · · ·	• • •	• •
11)☐ The oath or declaration is objected to by the	Examiner. Note the attache	d Office Action or form PTO-15	<b>)</b> 2.
Priority under 35 U.S.C. § 119			
12) Acknowledgment is made of a claim for fore a) All b) Some * c) None of:  1. Certified copies of the priority docum 2. Certified copies of the priority docum 3. Copies of the certified copies of the papplication from the International Bur * See the attached detailed Office action for a	ents have been received. ents have been received in a priority documents have been reau (PCT Rule 17.2(a)).	Application No n received in this National Stag	e
Attachment(s)			
<ol> <li>Notice of References Cited (PTO-892)</li> <li>Notice of Draftsperson's Patent Drawing Review (PTO-948)</li> <li>Information Disclosure Statement(s) (PTO-1449 or PTO/SB. Paper No(s)/Mail Date</li> </ol>	Paper No	Summary (PTO-413) (s)/Mail Date Informal Patent Application (PTO-152)	

## **DETAILED ACTION**

This action is in response to the applicant 's communication filed on 7/19/2004.

## Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claims 1-4, 7-8 are rejected under 35 U.S.C. 102(e) as being anticipated by Lee et al.

Lee et al teaches a method of making surface acoustic wave device (SAW) (see col.1, lines 10-15) by the following process steps; depositing polymeric layer "106" on substrate "104"; providing a template of polymer mold"108" having recess "108 " and protrusions formed on the surface thereof is pressed to the polymer layer "106", which is formed on the piezoelectric substrate "104" so as to form resist groove pattern "106 b". ( see fig. 1A-1E; 3A-3C; 4A-4C). Lee et al teaches the process can be used to form different devices including surface acoustic wave device, where the substrate must be piezoelectric material to form electrode pattern or wiring using polymer pattern "106" (see col. 3, lines 35-36).

With respect to claim 3; material layer "404" is formed on the substrate prior to formation of photo resist "406", wherein material layer is conductive layer such as metal and forming electrode pattern by patterning electrode film (see col. 5, lines 1-17). In Fig. 3 C the patterned layer "308" is formed of metal either copper or aluminum (see col. 4, lines 55-57).

With respect to claim 8, the roughness of the mold is 500 nm to 600 nm, which give the same roughness in the polymer layer "106". Since the distance between two projections in the polymer layer "108' is 500 nm to 600 nm, the projection must be less than 0.4 microns, which mean the width of the final electrode pattern is less than 0.4 microns, in fig. 2A the distance of separation is larger than the width of the electrode.

With respect to claim 7, ashing is inherent in the invention of Lee et al because ashing the photo resist is essential for curing (see col.1, lines 30-31).

Claim 5-6 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

Applicant is required to provide English translation of the foreign priority document in an effort to perfect the foreign priority see MPEP 706.02 (b)

Art Unit: 2812

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. Cho et al (2001-0036173) also teaches plastic template '230" by using x-ray lithography not by electron beam lithography.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Savitri Mulpuri whose telephone number is 571-272-1677. The examiner can normally be reached on Mon –Fri from.8-4.30.p.m

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Lebentritt, can be reached on 571-272-1873. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Savitri Mulpuri Primary Examiner Art Unit 2812